# LEAKAGE POWER OPTIMIZED SEQUENTIAL CIRCUITS FOR USE IN NANOSCALE VLSI SYSTEMS

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### Abstract

As the density and operating speed of CMOS VLSI chips increases, leakage power dissipation becomes more and more significant. Therefore it is necessary to reduce the leakage power of portable battery operated devices. This paper proposes three power reduction techniques such as transistor stacking, self-adjustable voltage level circuit and reverse body bias for use in sequential circuits like D flip-flops and shift register. This work analyses the power of three different implementations of D flip-flops using pass transistors, transmission gates and gate diffusion input gates. All the designs are simulated with and without the application of leakage reduction techniques and the readings are presented. Also two bit, four bit and eight bit shift registers are simulated with stack and reverse body bias leakage reduction techniques. The circuits are simulated with MOSFET models of level 54 using HSPICE in 65 nm process technology with a supply voltage of 1 volt. Simulation results show that the proposed pass transistor based D flip-flop circuit has the least leakage power dissipation. In the case of shift registers the combined stack and reverse body bias method gives minimum leakage power of 19.51nW, 32.16nW and 98.34nW for two bit, four bit and eight bit shift registers respectively.

Keywords: Leakage power, pass transistors, process technology, stacking effect, transmission gates.

# 1. Introduction

Increasing demand for mobile electronic devices such as cellular phones, laptop computers and personal digital assistants requires the use of power efficient VLSI circuits. To minimize the power consumption and to increase the battery life time, the supply voltage  $V_{dd}$  has been scaled down continuously. But the propagation delay  $T_{pd}$  of a circuit is inversely proportional to the square of the difference between the supply voltage  $V_{dd}$  and the threshold voltage  $V_t$  of the transistors. So scaling down the supply voltage, without scaling down the threshold voltage increases the propagation delay. However the threshold voltage scaling results in substantial increase of sub-threshold leakage current, which increases the leakage or static power dissipation of the VLSI circuits [1]. Leakage power dissipation is the power dissipated by the circuit when it is in sleep mode or standby mode. Leakage power is given by [2]

$$P_{leak} = I_{leak} * V_{dd}$$
(1)

where I<sub>leak</sub> is the leakage current that flows in a transistor when it is in off state. This power dominates dynamic power especially in deep submicron circuits and also in circuits that remains in idle mode for a long time such as cell phones. Therefore in this paper the focus is on the reduction of leakage power dissipation. The leakage current consists of various components, such as sub-threshold leakage, gate leakage, reverse-biased junction leakage, gate-induced drain leakage [3]. Among these, sub-threshold leakage and gate leakage are dominant. The sub-threshold leakage current of a MOS device can be modeled as follows [2]:

$$I_{subth} = I_0 \exp[(V_{gs} - V_t) / (n V_T)] [1 - \exp(-V_{ds} / V_T)]$$
(2)

And 
$$I_0 = \mu_{eff} C_{ox} (W/L) V_T^2$$
 (3)

where  $\mu_{eff}$  is the electron/hole mobility,  $C_{ox}$  is the gate capacitance per unit area, W and L are width and length of the channel respectively, Vt is the threshold voltage, n is the sub-threshold swing co-efficient,  $V_T$  is the thermal voltage,  $V_{gs}$  is the transistor gate to source voltage and  $V_{ds}$  is the drain to source voltage. This paper is organized as follows: Section 2 gives the related work in the area of flip-flop design. In section 3 we present three different designs of D flip-flops using pass transistors, transmission gates and Gate-Diffusion Input (GDI) gates. Section 4 describes three leakage reduction techniques such as transistor stacking, self-adjustable voltage level circuit and reverse body bias that are applied to the above designs. Section 5 presents the simulation results of the flip-flops and shift registers with and without the leakage reduction techniques and section 6 gives the conclusion.

### 2. Related Work

In [4] Hamid *et al.* proposes a conventional data-retention scheme which uses a balloon latch applied to a transmission gate flip-flop. In this the balloon latch and some switches which are not in the critical paths use high threshold voltage transistors to reduce their leakage power. This scheme requires extra data-preserving balloon latches and complicated timing for transferring data back and forth between balloon latches and flip-flops on any transition from power down to active mode and vice versa. In [5] David Levacq designed an ultra low power flip-flop using two ultra-low leakage diodes and analysis of master slave latches and flip-flops is discussed in [6]. In [7] Linfeng *et al.* proposes a new transmission gate flip-flop based on dual threshold CMOS technique to reduce it's leakage power. In this low threshold transistors are assigned to critical paths of the circuits to enhance the performance, while high threshold transistors are assigned to non-critical paths to reduce the leakage current. In [8] Morgenstein *et al.* describes the implementation of D flip –flop using GDI gates. The analysis of single edge triggered flip flops is presented by D. Markovic *et al.* in [9] and Nedovic *et al.* in [10] describes the design of dual edge triggered flip-flops. Sagi Fisher *et al.* in [11] proposes two architectures for implementing flip-flop cells by integrating a GDI multiplexer in their design.

## 3. CMOS Implementation of D flip flops

In this section three different implementations of D flip-flops in CMOS logic are presented. The D flip-flop combines a pair of master and slave D latch. Design – I uses pass transistors and inverters for the master-slave latches [12] as shown in figure 1. The two chained inverters are in memory state when the PMOS loop transistor is on, that is when clk = 0. Other two chain inverters on the right hand side acts in the opposite way. The flip-flop changes its state during the falling edge of the clock.

Figure 2 shows the design – II that uses transmission gates and inverters [12]. At the negative edge of the clock, transmission gates T1 and T4 are ON and transmission gates T2 and T3 are OFF. During this time the slave maintains a loop through two inverters P3, P4 and T4. Now the previous triggered value from Din is stored in the slave. At the same time master latches next state but as T3 is OFF it is not passed to slave. At the positive clock edge T2 and T3 are turned ON and the new latched value passes to slave through the loop of two inverters P1, P2 and T2.

Figure 3 shows design –III with master-slave connection of two GDI D-latches [8]. In this the body gates are responsible for the state of the circuit. These gates are controlled by the clock (clk) signal and create two alternative paths. One for transparent state of the latch ,when the clk is low and the signals are propagating through PMOS transistors .The other one is for the holding state of the latch ,when the clk signal is high and internal values are maintained due to conduction of the NMOS transistors. The inverters are responsible for maintaining the complementary values of the internal signals and the circuit outputs.

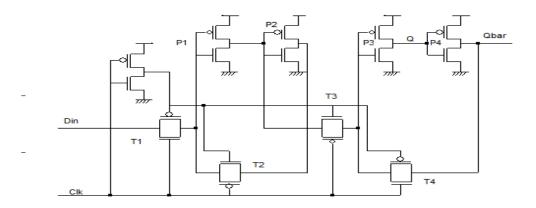


Fig. 1. D flip-flop using pass transistors

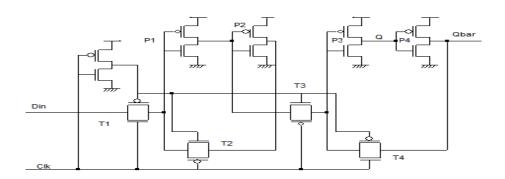


Fig. 2. D flip-flop using transmission gates

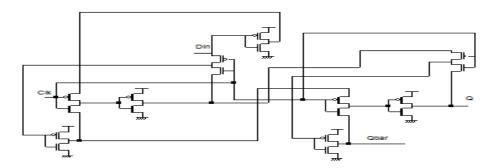


Fig. 3. D flip-flop using GDI gates

# 4. Proposed Leakage Current Reduction Techniques

In this section three leakage reduction techniques namely transistor stacking, self-adjustable voltage level circuit and reverse body bias that are applied to the above circuits are described.

# 4.1. Leakage current control using transistor stack

The leakage current flowing through a stack of series connected transistors reduces when more than one transistor of the stack is turned OFF. This effect is known as the "Stacking Effect" [13]. When two or more transistors that are switched OFF are stacked on top of each other [refer figure 4(a)], then they dissipate less

leakage power than a single transistor that is turned OFF [refer figure 4(b)]. This is because each transistor in the stack induces a slight reverse bias between the gate and source of the transistor right below it, and this increases the threshold voltage of the bottom transistor making it more resistant to leakage. Therefore in figure 4(a) transistor T2 leaks less current than transistor T1 and T3 leaks less than T2. Hence the total leakage current through the transistors T, T2 and T3 is decreased as it flows from Vdd to Gnd. So Ileak1 is less than Ileak2. If natural stacking of transistors do not exist in a circuit, then to utilize the stacking effect a single transistor of width W is replaced by two transistors each of width W/2 [refer figure 4(c)].

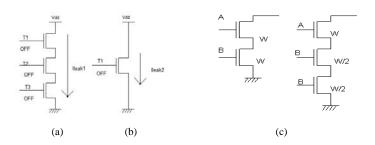


Fig. 4. Transistor stacking effect

## 4.2. Self-adjustable voltage level circuit

Figure 5 shows the general self-adjustable voltage level circuit [14], where  $V_{dd}$  is the supply voltage and  $V_L$  is the output voltage of this circuit, which is applied to any load circuit. (In this paper D flip-flop is the load circuit). During the active mode (when SL=0), this circuit supplies maximum supply voltage to the load circuit through the ON PMOS transistor (P1) so that the load circuit can operate quickly. During the standby mode (SL=1), it provides slightly lower supply voltage to the load circuit through the weakly ON NMOS transistors (N1, N2, N3, ---Nm). So the voltage applied to the load circuit is given by

$$V_{L} = V_{dd} - V_{n} \tag{4}$$

where  $V_n$  is the voltage drop of m weakly ON NMOS transistors. The drain to source voltage  $V_{dsn}$  of the OFF NMOS in the standby mode is expressed as

$$V_{dsn} = V_L - V_{ss} = V_L$$
 (5)

 $V_{dsn}$  can be decreased by increasing  $V_n$  that is increasing m, the number of NMOS transistors. When  $V_{dsn}$  is decreased, the drain- induced – barrier-lowering (DIBL) effect is decreased and this in turn increases the threshold voltage  $V_{tn}$  of NMOS transistors. Consequently the sub- threshold leakage current of the OFF MOSFETs decreases, so leakage power is minimized, while data are retained.

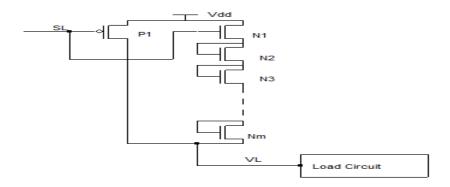


Fig. 5. D flip-flop with self-adjustable voltage level (SAL) circuit

# 4.3. Reverse body bias (RBB)

This is an effective approach to reduce leakage power. In this method, when the circuit enters the standby mode, RBB is applied to increase the threshold voltage Vt of the transistors and this decreases the sub-threshold leakage current. Vt is related to the reverse bias voltage between the source and body Vsb by the following equation [15]:

$$Vt = Vto + \gamma \left\{ \left( \sqrt{2\phi_f} + \sqrt{8b} \right) - \left( \sqrt{2\phi_f} \right) \right\}$$
 (6)

where Vto is the zero bias Vt for Vsb = 0volt,  $\phi_f$  is a physical parameter and  $\gamma$  is a fabrication-process parameter. Modification of Vt can be achieved by changing |Vsb|. This method can be either applied at the full chip level or a finer granularity. The advantage of this method is that it can be implemented without incurring any delay penalty. The key issue is that the range of threshold adjustment is limited, which in turn limits the amount of leakage reduction.

## 5. Simulation Results and Discussion

In this work three designs of D flip-flops have been implemented in 65 nm CMOS process technology. The leakage power dissipation of the above circuits are compared with and without the power reduction techniques. The net lists of the circuits are extracted and simulated with BSIM4 models of MOSFET [16]. The simulations are done in HSPICE with a supply voltage of 1 volt, at a temperature of 27° C with a load capacitance of 50fF. The figure 6 shows the input-output waveforms of D flip-flop. The simulation results of D flip-flop with and without transistor stacking technique is presented in table 1. In this the leakage power reduction is more (13.05%) in D flip-flop designed using transmission gates. Table 2 shows the leakage power reduction using SAL technique and the reduction is maximum (34.67%) in transmission gate based D flip-flop. The design of D flip flops using pass transistors gives the minimum leakage current and using this flip flop 2-bit, 4-bit and 8-bit shift registers are implemented. The leakage power of the shift registers are compared with and without the stack and reverse body bias reduction techniques. The simulation results are shown in table 3 and for the shift registers the combined effect of RBB and stack method gives the leakage power. Figure 7 shows the percentage reduction of leakage power in flip flops and figure 8 shows the leakage power in shift registers.

# 6. Conclusion

Low leakage power D flip-flop circuits are proposed in this work. The leakage power of three designs of D flip-flops are analyzed in 65 nm process technology. The percentage reduction of leakage power is more with the proposed SAL technique. The design of D flip-flop using pass transistors with SAL technique gives the minimum leakage power. Therefore for low leakage power applications D flip flop design using pass transistors can be used. In the case of shift registers leakage reduction is more for the combined approach of stacking and RBB technique.

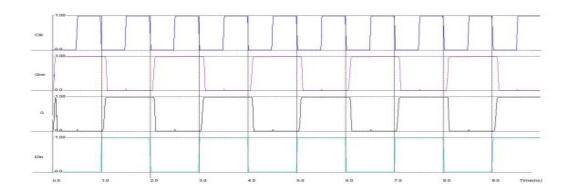


Fig. 6. Input -output waveforms of D FF

Table 1. Leakage power of D flip-flops with stacking.

D FF Circuit	Pleak	% Reduction in Pleak		
	Without stack	With stack	70 Reduction in Fleak	
Pass transistors	16.42	14.95	8.95	
Transmission gates	29.65	25.78	13.05	
GDI gates	25.74	23.06	10.41	

Table 2. Leakage power of D flip-flops with SAL circuit.

	Pleak (nW)		.,	
D FF Circuit	Without SAL	With SAL	% Reduction in Pleak	
Pass transistors	16.42	13.46	18.03	
Transmission gates	29.65	19.37	34.67	
GDI gates	25.74	20.94	18.64	

Table 3. Leakage power of shift registers with leakage reduction techniques

S.No.		Pleak of shift register (nW)			
	Reduction Technique used	2-bit	4-bit	8-bit	
1	Base Case	26.43	51.84	119.92	
2	Stack	23.94	38.56	107.65	
3	RBB	25.17	49.35	114.18	
4	RBB + Stack	19.51	32.16	98.34	

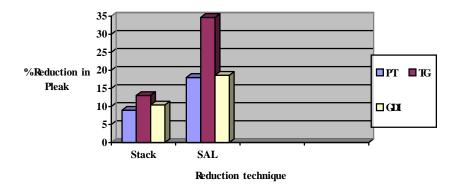


Fig. 7. % Leakage reduction in flip flops

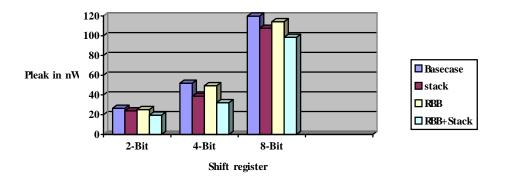


Fig. 8. Leakage power in shift registers

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